

Envure System™: Envure NA™

High Purity Non-Aqueous Components for Microelectronic Formulations

▶ **SACHEM's Envure NA™** non-aqueous strong bases can be used in photoresist strippers, electronic surface cleaners, edge bead removers and for other microelectronic applications requiring little or no water.

▶ **Features of Envure NA™**

Multiple solvents available to expand formulation options

- Methanol-based products allow for ease of solvent replacement

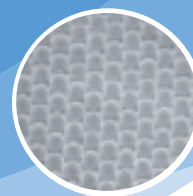
Enhanced organic solubility of polymeric residues

Low metal ion contamination

- In line with microelectronic industry standards (ppb)

Low water content minimizes corrosion

- Reduce metal-loss during stripping
- Diminish notching of metal lines
- Resist galvanic corrosion



Envure NA™

SACHEM's Envure NA™ line includes methanol and propylene glycol solvent-based products. Datasheets are available on www.sacheminc.com for further review.

- | |
|--|
| ▶ Envure NA™ 1011 Tetramethylammonium Hydroxide in Methanol |
| ▶ Envure NA™ 1031 Benzyltrimethylammonium Hydroxide in Methanol |
| ▶ Envure NA™ 1041 Dimethyldipropylammonium Hydroxide in Methanol |
| ▶ Envure NA™ 1051 Tetrabutylammonium Hydroxide in Methanol |
| ▶ Envure NA™ 2011 Tetramethylammonium Hydroxide in Propylene Glycol |
| ▶ Envure NA™ 2021 Tetraethylammonium Hydroxide in Propylene Glycol |
| ▶ Envure NA™ 2031 Benzyltrimethylammonium Hydroxide in Propylene Glycol |
| ▶ Envure NA™ 2041 Dimethyldipropylammonium Hydroxide in Propylene Glycol |
| ▶ Envure NA™ 2051 Tetrabutylammonium Hydroxide in Propylene Glycol |



SACHEM's unique chemical understanding supports our customers in final application conditions and performance. Talk to us about your specific solvent need! We love to talk chemistry!

